

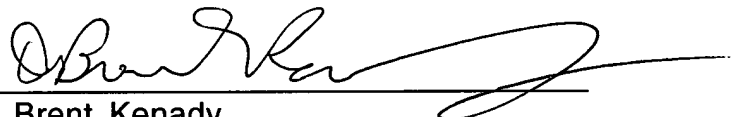
REMARKS

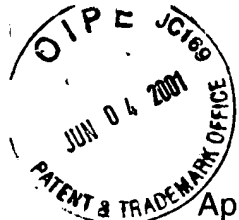
The Examiner has required restriction under 35 U.S.C. §121 between claims 21-28 (Group I) and 1-20 (Group II). Applicant hereby elects claims 1-20 (Group II) for prosecution on the merits.

Claims 21-28 (Group I) have been canceled. Claims 1-20 (Group II) remain pending in the application for consideration.

Respectfully submitted,

Dated: 6-1-01

By: 
D. Brent Kenady
Reg. No. 40,045



Application Serial No. 09/332,271
Filing Date June 11, 1999
Inventor Klaus Florian Schuegraf et al.
Assignee Micron Technology, Inc.
Group Art Unit 2815
Examiner E. Lee
Attorney's Docket No. MI22-532
Title: Methods for Forming Wordlines, Transistor Gates, and Conductive
Interconnects, and Wordline, Transistor Gate, and Conductive Interconnect
Structures

**VERSION WITH MARKINGS TO SHOW CHANGES MADE ACCOMPANYING
RESPONSE TO MAY 22, 2001 OFFICE ACTION**

In the Claims

The claims have been amended as follows. Underlines indicate insertions
and ~~strikeouts~~ indicate deletions.

Please cancel claims 21-28.